

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:)	Docket No.:	020732-97.668
)		(7493)
Applicants: RATH, Melissa K., et al.)	Conf. No.:	4823
Application No.: 10/792,038)	Art Unit:	1752
Date Filed: March 3, 2004)	Examiner:	LE, Hoa Van
Title: COMPOSITION AND PROCESS FOR)	Customer No.:	24239
POST-ETCH REMOVAL OF)		
PHOTORESIST AND/OR)		
SACRIFICIAL ANTI-REFLECTIVE)		
MATERIAL DEPOSITED ON A)		
SUBSTRATE)		

AMENDMENT RESPONDING TO APRIL 19, 2007 OFFICE ACTION IN UNITED STATES PATENT APPLICATION NO. 10/792,038

Mail Stop Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

This responds to the April 19, 2007 Office Action in the above-identified application.

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the April 19, 2007 Office Action are set out in the **Section II (Remarks)** hereof.